



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Leonard Forbes et al.

Examiner: Unknown

Serial No.:

Unknown

Group Art Unit: Unknown

Filed:

Herewith

Docket: 303.324US4

Title:

TRANSISTOR WITH VARIABLE ELECTRON AFFINITY GATE AND

METHODS OF FABRICATION AND USE

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

When the above-identified patent application is taken up for consideration, please amend the application as follows:

IN THE SPECIFICATION

On page 1, line 5, before "Field of the Invention", please insert the sentence, application is a continuation of U.S. Serial No. 08/903,452, filed on July 29, 1997.--

IN THE CLAIMS

Please cancel claims 1-35 without prejudice and add the following new claims 36-100.

36. A transistor comprising:

a source region, a drain region, a channel region between the source and drain regions, and a gate separated from the channel region by an insulator, the gate formed of a silicon carbide compound $Si_{1x}C_{x}$, wherein x is greater than 0.5 to establish a desired value of a barrier energy between the gate and the insulator.

37. A transistor comprising:

a source region, a drain region, a channel region between the source and drain regions, and a gate separated from the channel region by an insulator, the gate formed of a silicon carbide compound $Si_{1-x}C_x$, wherein x is selected at a predetermined value approximately between 0.5 and 1.0 to establish a desired value of a barrier energy between the gate and the insulator.

38. The transistor of claim 36, wherein the value of the barrier energy is approximately between 0 eV and 2.8 eV.

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